

Form PTO-1449 (modified)

List of Patents and Publications for Applicant

INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

Atty. Docket No.
2000.071100/SFDSerial No.
09/897,576Applicants
Richard J. Markle, et al.Filing Date:
July 2, 2001Group:
2877U.S. Patent Documents
See Page 1

Foreign Patent Documents

Other Art
See Page 1-2

U.S. Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Name	Class	Sub Class	Filing Date of App.
AV	A1	6,051,348	4/18/00	Marinero <i>et al.</i>	430	30	
AV	A2	6,245,584 B1	6/12/01	Marinero <i>et al.</i>	438	14	
	A3						

Foreign Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Country	Class	Sub Class	Translation Yes/No

Other Art (Including Author, Title, Date Pertinent Pages, Etc.)

Exam. Init.	Ref. Des.	Citation
	C1	
	C2	
	C3	
	C4	
	C5	
	C6	

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EXAMINER: INITIAL IF REFERENCE CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED. INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.

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U.S. Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Name	Class	Sub Class	Filing Date of App.
SN	A1	5,880,838	3/9/1999	Marx, et al.	356	351	6/5/1996
SN	A2	5,867,276	2/2/1999	McNeil, et al.	356	445	3/7/1997
SN	A3	5,393,624	2/28/1995	Ushijima	430	30	8/3/1992

Foreign Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Country	Class	Sub Class	Translation Yes/No

Other Art (Including Author, Title, Date Pertinent Pages, Etc.)

Exam. Init.	Ref. Des.	Citation
SN	C1	Bishop <i>et al.</i> , "Use of Scatterometry for resist process control," <i>SPIE Integrated Circuit Metrology, Inspection and Process Control</i> , 1673:441-452, 1992.
SN	C2	Hickman <i>et al.</i> , "Use of diffracted light from latent images to improve lithography control," <i>SPIE Integrated Circuit Metrology, Inspection and Process Control</i> , 1464:245-257, 1991.
SN	C3	McNeil <i>et al.</i> , "Scatterometry applied to microelectronics processing - Part 1," <i>Solid State Technology</i> , 37(3):29-56, 1993.
SN	C4	Miller and Mellicamp, "Development of an end-point detection procedure for the post-exposure bake process," <i>Integrated circuit metrology, inspection, and process control IX: 20-22, February, 1995, Santa Clara, California, SPIE Integrated Circuit Metrology, Inspection and Process Control</i> , 2439:78-88, 1995.
SN	C5	Milner <i>et al.</i> , "Latent image exposure monitor using scatterometry," <i>SPIE Integrated Circuit Metrology, Inspection and Process Control</i> , 1673:274-283, 1992.
SN	C6	Prins <i>et al.</i> , "Scatterometric sensor for PEB process control," <i>Metrology, inspection, and process control for microlithography, X: 11-13, March, 1996, Santa Clara, California, SPIE Integrated Circuit Metrology, Inspection and Process Control</i> , 2725:710-719, 1996.

EXAMINER:

Sung H. Kim

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Exam. Init.	Ref. Des.	Citation
SN	C7	Raymond <i>et al.</i> , "Multiparameter process metrology using scatterometry," In: <i>Optical characterization techniques for high-performance microelectronic device manufacturing II</i> , SPIE - The International Society for Optical Engineering, 2638:84-93, Austin, Texas, October 25-26, 1995.
SN	C8	Raymond <i>et al.</i> , "Scatterometric sensor for lithography," In: <i>Manufacturing process control for microelectronic devices and circuits</i> , SPIE - The International Society for Optical Engineering, 2336:37-49, Austin, Texas, October 20-21, 1994.
SN	C9	Sturtevant <i>et al.</i> , "Post-exposure bake as a process-control parameter for chemically-amplified photoresist," <i>Metrology, inspection, and process control for microlithography</i> , VII:2-4, March, 1993, Santa Jose, California, SPIE Integrated Circuit Metrology, Inspection and Process Control, vol. 1926, 1993.
SN	C10	Sturtevant <i>et al.</i> , "Use of scatterometric latent image detector in closed loop feedback control of linewidth," <i>SPIE Integrated Circuit Metrology, Inspection and Process Control</i> , 2196:352-359, 1994.

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SN/PR

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